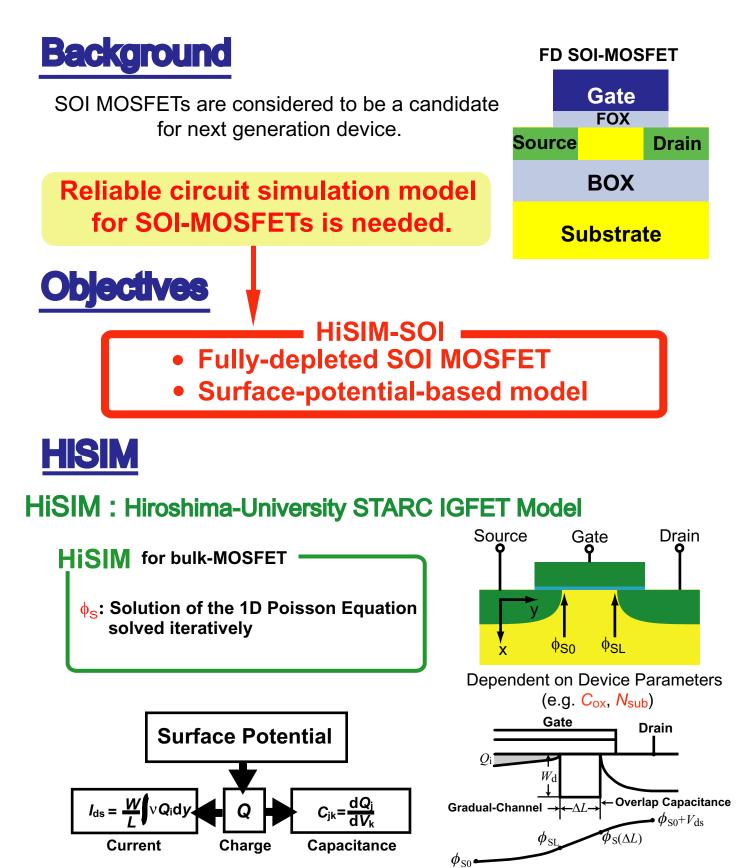
## HiSIM-SOI: Complete Surface-Potential-Based Fully-Depleted SOI-MOSFET Model for Circuit Simulation

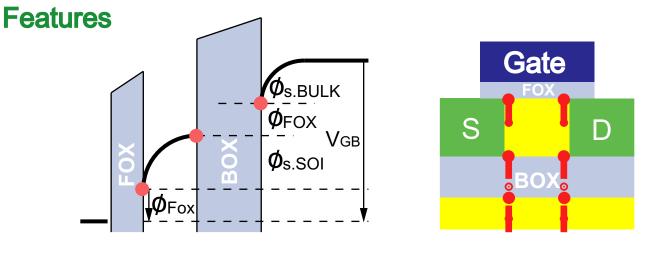
N. Sadachika, D. Kitamaru, Y. Uetsuji, D. Navarro, M. Mohd. Yusoff, T. Ezaki, H. J. Mattausch, M. Miura-Mattausch, \*S. Baba Graduate School of Advanced Sciences of Matter, Hiroshima University 1-3-1, Kagamiyama, Higashi-Hiroshima, 739-8530, Japan \*Oki Electric Industry, Hachiouji 193-8550, Tokyo

Phone: +81-824-24-7637 Fax: +81-824-24-7638 E-mail: sadatika@hiroshima-u.ac.jp



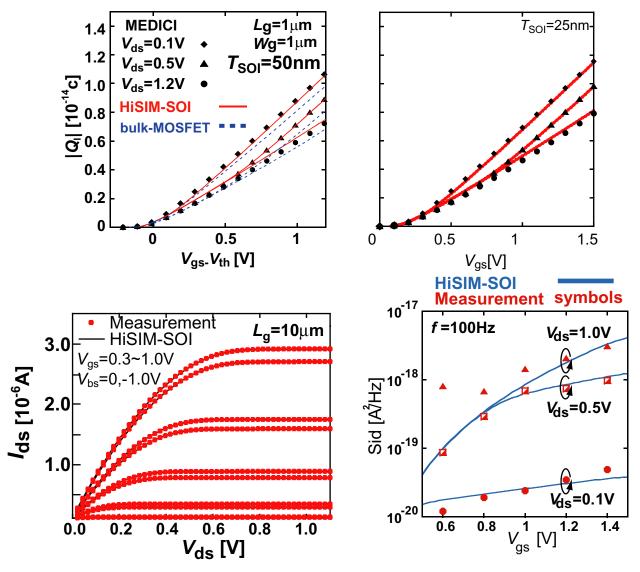
Accurate calculation of  $\varphi_{\text{SO}}$  and  $\varphi_{\text{SL}}$  is the core for HiSIM





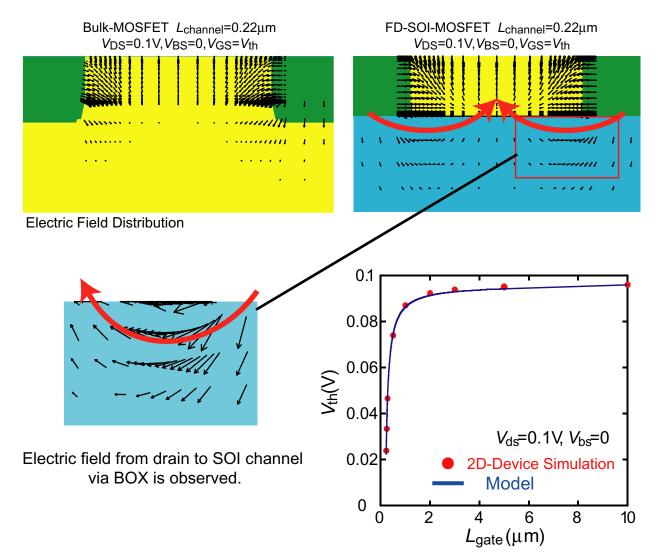
HiSIM-SOI
Calculates three surface potentials
Iterative surface potential calculation

## (1) Charge, I-V and 1/f Noise Calculation Results

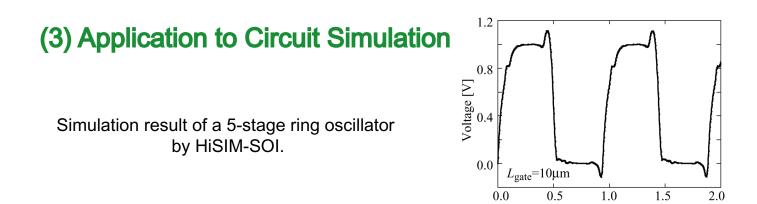


*I-V* and 1/*f* noise characteristics calculated by HiSIM-SOI are in good agreement with measured results.

## (2) Short Channel Effect in SOI MOSFET



Short channel effect model considering detour filed describes  $V_{\text{th}}$ - $L_{\text{q}}$  characteristics accurately.



HiSIM-SOI achives stable calculation.

 $t \, [\mu sec]$ 



- We have developed the circuit simulation model HiSIM-SOI for SOI MOSFET.
- Inversion charge characteristics calculated by HiSIM-SOI show good agreement with 2-D device simulation results.
- HiSIM-SOI reproduces measured *I-V* and 1/*f* noise characteristics accurately.
- Short channel effect model for SOI-MOSFET is developed.
- HiSIM-SOI is implemented into the circuit simulator SPICE 3F5.